

# ISO 16531:2020 (E)

## Surface chemical analysis — Depth profiling — Methods for ion beam alignment and the associated measurement of current or current density for depth profiling in AES and XPS

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### Contents

	Foreword
	Introduction
1	Scope
2	Normative references
3	Terms, definitions, symbols and abbreviated terms
4	System requirements
4.1	General
4.2	Limitations
5	Ion beam alignment methods
5.1	General
5.2	Important issues to be considered prior to ion beam alignment
5.3	Alignment using circular-aperture Faraday cup
5.4	Alignment using elliptical-aperture Faraday cup
5.5	Alignment using images from ion-induced secondary electrons during ion beam rastering
5.6	Alignment in X-ray photoelectron microscope/photoelectron imaging system
5.7	Alignment by observing direct ion beam spot or crater image during and after ion sputtering
5.8	Alignment by observing phosphor sample
6	When to align and check ion beam alignment
Annex A	(informative) Comparison of AES depth profiles with good/poor ion beam alignment
Annex B	(informative) Alignment using cup with co-axial electrodes

Page count: 19